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## Key Factors for the Development of Silicon Quantum Dot Solar Cell

<u>김경중</u><sup>1,3</sup>, 박재희<sup>2</sup>, 홍승휘<sup>1,2</sup>, 최석호<sup>2</sup>, 황혜현<sup>1,3</sup>, 장종식<sup>4</sup>

<sup>1</sup>한국표준과학연구원 산업측정표준본부, <sup>2</sup>경희대학교 물리학과, <sup>3</sup>과학기술연합대학원대학교 나노및바이오 표면과학과, <sup>4</sup>충북대학교 물리학과

Si quantum dot (QD) imbedded in a  $SiO_2$  matrix is a promising material for the next generation optoelectronic devices, such as solar cells and light emission diodes (LEDs). However, low conductivity of the Si quantum dot layer is a great hindrance for the performance of the Si QD-based optoelectronic devices. The effective doping of the Si QDs by semiconducting elements is one of the most important factors for the improvement of conductivity. High dielectric constant of the matrix material  $SiO_2$  is an additional source of the low conductivity. Active doping of B was observed in nanometer silicon layers confined in SiO<sub>2</sub> layers by secondary ion mass spectrometry (SIMS) depth profiling analysis and confirmed by Hall effect measurements. The uniformly distributed boron atoms in the B-doped silicon layers of [SiO<sub>2</sub>(8 nm)/B-doped Si(10 nm)]<sub>5</sub> films turned out to be segregated into the Si/SiO<sub>2</sub> interfaces and the Si bulk, forming a distinct bimodal distribution by annealing at high temperature. B atoms in the Si layers were found to preferentially substitute inactive three-fold Si atoms in the grain boundaries and then substitute the four-fold Si atoms to achieve electrically active doping. As a result, active doping of B is initiated at high doping concentrations above  $1.1 \times 10^{20}$  atoms/cm<sup>3</sup> and high active doping of  $3 \times 10^{20}$  atoms/cm<sup>3</sup> could be achieved. The active doping in ultra-thin Si layers were implemented to silicon quantum dots (QDs) to realize a Si QD solar cell. A high energy conversion efficiency of 13.4% was realized from a p-type Si QD solar cell with B concentration of  $4 \times 1^{20}$  atoms/cm<sup>3</sup>. We will present the diffusion behaviors of the various dopants in silicon nanostructures and the performance of the Si quantum dot solar cell with the optimized structures.

Keywords: Silicon, Quantum dot, Solar cell, Doping, Activation